



G. 1A (Prior Art)

The diagram illustrates a conventional optical lithography system. At the top, a light source (LA) emits light through an exposure mask (EX). The light then passes through a series of lenses (IL, AM, IN, CO) and is focused onto a photoresist layer (RE) on a substrate (RT). The substrate is mounted on a stage (WS) which includes a wafer (WT). A coordinate system (X, Y, Z) is shown. A detailed view of the photoresist layer (RE) shows a grid pattern with a central region (C) and peripheral regions (P1, P2). A coordinate system (X, Y, Z) is also shown for the detailed view.





REPLACEMENT SHEET

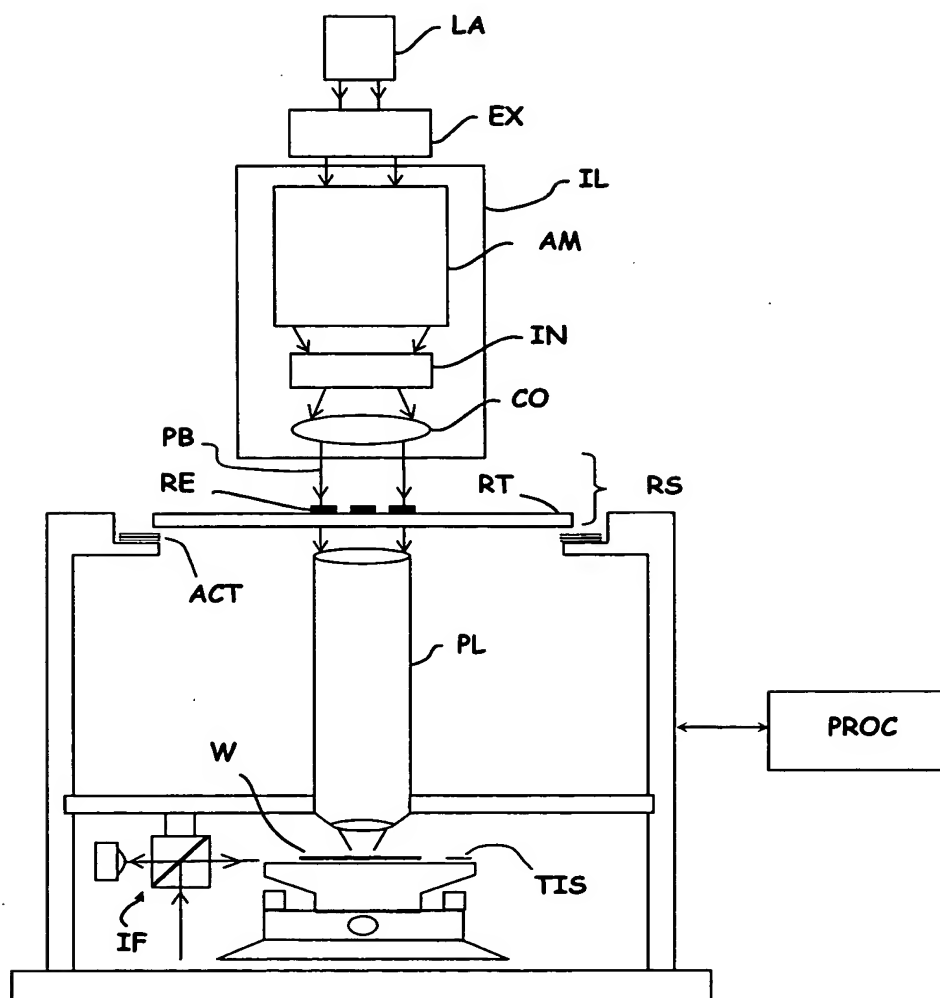


FIG. 2E